

CURRICULUM VITAE

Personal information

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Date and place of birth: 12th October 1978, PROSTEJOV
Citizenship: Czech Republic
Marital status: single



Education

2002 – now **Fellow of IMPRS-AM**
International Max Planck Research School for Advanced Materials
Synthetic Nanostructures – Carbon Nanotubes

1997 – 2002 **University of Pardubice**
Faculty of Chemical Technology
Material Science

- 6/2002 MSc. Degree Material Science
- 9/2000 BSc. Degree Chemistry and technical chemistry
- 2/2000 Certificate of applied medicine for science engineers

1990 – 1997 **Gymnasium Jiriho Wolkra**
Secondary Education focused to natural sciences

- Majors: Chemistry, Programming, Czech, English

Languages

Czech	native language
English	fluent
French	basic
German	basic

Skills

- Preparation & Characterization of Carbon nanomaterials
- Transmission Electron Microscopy & EELS
- Thin films deposition techniques & glassy bulk material synthesis
- Characterization of thin films (UV/VIS, NIR, FT RAMAN spectroscopy)
- Characterization of surfaces (AFM, SEM, optical microscopy)
- Wet Etching Technology, diffractive optical elements (DOE) design
- Unix/Linux & LaTeX, Apple MAC OS X (Panther and Tiger), Windows, Office
- Basic Network Administration, security, XHTML/CSS
- PC Hardware diagnostics and basic programing skills

Professional experience

- **Steacie Institute for Molecular Sciences, NRC**, Ottawa, ON, Canada, Visiting Scientist, *Laser Ablation study for nanocarbons preparation*, 4/2004
- **Yangtze Nanomaterials Co. Ltd**, Shanghai, China, Visiting Scientist, *Arc Discharge preparation of Carbon Nanotubes*, 11/2003-12/2003
- **Institut für Physikalische Hochtechnologie (IPHT) e.V.** Jena, Visiting Scientist, *non-crystalline semiconductor thin layers structurizing by holographical exposure, laser lithography and consequent wet etching*, 7/2001 - 9/2001
- **AVX Czech republic**, Kyocera group company, Engineering dept.-chemical process engineer, *tantalum capacitor surface layer oxidation development*, 6/2000 - 9/2000
- **AISEC**: Business Presentation and HR projects, Kontakt 2000, 1999-2000
- **Department of Inorganic Chemistry**, *Science Assistantship*, 1998-2002

References

Prof. Siegmund Roth, Ph.D.

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Additional information

I have never been convicted of a criminal offence.
I am non-smoker (I smoke pipe rarely)
I hold driving license
I hold pilot license

The facts stated in this C.V. are true and correct to the best of my knowledge.

March 3, 2006

Ing. Jirka Cech